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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.	
09/910,638	07/20/2001	Nathan R. Brown	500200.05	500200.05 3241	
27076	7590 07/02/2004		EXAMINER		
DORSEY & WHITNEY LLP			GRANT, ALVIN J		
INTELLECTUAL PROPERTY DEPARTMENT SUITE 3400 1420 FIFTH AVENUE SEATTLE, WA 98101		ART UNIT	PAPER NUMBER		
		3723			
			DATE MAILED: 07/02/2004		

Please find below and/or attached an Office communication concerning this application or proceeding.

				<i>f</i>					
Office Action Summary		Application	No.	Applicant(s)					
		09/910,638		BROWN, NATHAN R.					
		Examiner		Art Unit					
		Alvin J Grant		3723					
The MAILING DATE of this communication appears on the cover sheet with the correspondence address									
Period for Repl	-								
THE MAILIN - Extensions of the after SIX (6) M - If the period form of the period form	NED STATUTORY PERIOD FOR REPLY IG DATE OF THIS COMMUNICATION. Itime may be available under the provisions of 37 CFR 1.13 ONTHS from the mailing date of this communication. It reply specified above is less than thirty (30) days, a reply or reply is specified above, the maximum statutory period were within the set or extended period for reply will, by statute, ived by the Office later than three months after the mailing term adjustment. See 37 CFR 1.704(b).	36(a). In no event, y within the statutor will apply and will ex e, cause the applica	however, may a reply be time y minimum of thirty (30) days pire SIX (6) MONTHS from the ion to become ABANDONED	will be considered timely. the mailing date of this communication. (35 U.S.C. § 133).					
Status									
1)⊠ Respo	onsive to communication(s) filed on <u>24 M</u>	<u>1ay 2004</u> .							
2a)⊠ This a	ction is FINAL . 2b) This	action is non	-final.						
3)☐ Since	this application is in condition for allowar	nce except fo	formal matters, pros	secution as to the merits is					
closed	I in accordance with the practice under E	Ex parte Quay	le, 1935 C.D. 11, 45	3 O.G. 213.					
Disposition of	Claims								
4)⊠ Claim	☑ Claim(s) <u>54-56 and 58</u> is/are pending in the application.								
4a) Of	4a) Of the above claim(s) is/are withdrawn from consideration.								
5)∭ Claim	Claim(s) is/are allowed.								
6)⊠ Claim	Claim(s) <u>54-56 and 58</u> is/are rejected.								
7) Claim	(s) is/are objected to.								
8)∏ Claim	(s) are subject to restriction and/or	or election req	uirement.						
Application Pa	pers								
9) The specification is objected to by the Examiner.									
10) The drawing(s) filed on is/are: a) accepted or b) objected to by the Examiner.									
Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).									
Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d).									
11) <u></u> The oa	th or declaration is objected to by the Ex	xaminer. Note	the attached Office	Action or form PTO-152.					
Priority under	35 U.S.C. § 119								
 12) Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f). a) All b) Some * c) None of: 1. Certified copies of the priority documents have been received. 2. Certified copies of the priority documents have been received in Application No 3. Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)). * See the attached detailed Office action for a list of the certified copies not received. 									
Attachment(s) 1) Notice of References Cited (RTO 802) 1) Intention Summer (RTO 412)									
1) Notice of References Cited (PTO-892) 4) Interview Summary (PTO-413) Notice of Draftsperson's Patent Drawing Review (PTO-948) Paper No(s)/Mail Date									
3) 🛛 Information D	bisclosure Statement(s) (PTO-1449 or PTO/SB/08)	,	Notice of Informal Pa	tent Application (PTO-152)					
Paper No(s)/Mail Date <u>6/27/04</u> . 6) Other:									

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DETAILED ACTION

Claim Rejections - 35 USC § 103

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

Claims 54, 55, 56 and 58 are rejected under 35 U.S.C. 103(a) as being unpatentable over Yu '699 in view of White '070.

Yu discloses a method for removing material from a microelectronic substrate, comprising: engaging the microelectronic substrate with a planarizing medium, which includes a polishing pad; moving at least one of a first part of the microelectronic substrate and the planarizing medium relative to the other at a first rate; moving at least one of a second part of the microelectronic substrate and the planarizing medium inwardly relative to the other at a second rate less than the first rate; removing material from the first and second parts of the microelectronic substrate at approximately equal rates (or uniform rates) by biasing the first part of the microelectronic substrate against the planarizing medium with a first membrane portion having a first thickness and biasing the second part of the microelectronic substrate against the planarizing medium with a second membrane portion having a second thickness greater than the first thickness (column 2, lines 60-63); the second annular part of the microelectronic substrate positioned radially inwardly from the first annular part of the microelectronic substrate; the membrane has a first surface facing toward the microelectronic substrate and a second surface facing generally opposite the first surface (Fig. 7; and column 3, lines 4-22), and wherein biasing the microelectronic substrate against the planarizing medium includes biasing a generally flat support member against the second surface of the membrane. Yu does not specifically disclose a planarizing medium that includes advancing the polishing pad from a supply roller to a take-up roller. However, the use of linear polishing pads that extend between polishing wheels that move them in a linear direction, is well known in the art. White, for

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example, discloses the use of a planarizing medium that includes advancing the polishing pad from a supply roller to a take-up roller so as to move the used portion of the pad away from the planarizing zone thus providing for a clean pad during the planarizing process. It would have been obvious to one having ordinary skill in the art at the time the invention was made to have used a take-up roller in the apparatus of Yu as taught by White so as to move the used portion of the pad away from the planarizing zone thus providing for a clean pad during the planarizing process.

Response to Arguments

Applicant's arguments filed 24 May 2004 have been fully considered but they are not persuasive. In response to Applicant's arguments that the Yu reference fails to disclose, or suggest in any motivated sense that the planarization medium may be moved from a supply roller to a take-up roller, it has been held that the test for obviousness is not whether the features of one reference may be bodily incorporated into the other to produce the claimed subject matter but simply what the combination of references makes obvious to one of ordinary skill in the pertinent art. In re Bozek, 163 USPQ 545 (CCPA 1969).

Furthermore, White discloses the use of a planarizing medium that includes advancing the polishing pad from a supply roller to a take-up roller so as to move the used portion of the pad away from the planarizing zone thus providing for a clean pad during the planarizing process.

Double Patenting

The nonstatutory double patenting rejection is based on a judicially created doctrine grounded in public policy (a policy reflected in the statute) so as to prevent the unjustified or improper timewise extension of the "right to exclude" granted by a patent and to prevent possible harassment by multiple assignees. See *In re Goodman*, 11 F.3d 1046, 29 USPQ2d 2010 (Fed. Cir. 1993); *In re Longi*, 759 F.2d 887, 225 USPQ 645 (Fed. Cir. 1985); *In re Van Ornum*, 686 F.2d 937, 214 USPQ 761 (CCPA 1982); *In re Vogel*, 422 F.2d 438, 164 USPQ 619 (CCPA 1970);and, *In re Thorington*, 418 F.2d 528, 163 USPQ 644 (CCPA 1969).

A timely filed terminal disclaimer in compliance with 37 CFR 1.321(c) may be used to overcome an actual or provisional rejection based on a nonstatutory double patenting ground provided the conflicting application or patent is shown to be commonly owned with this application. See 37 CFR 1.130(b).

Effective January 1, 1994, a registered attorney or agent of record may sign a terminal disclaimer. A terminal disclaimer signed by the assignee must fully comply with 37 CFR 3.73(b).

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Claims 54, 55, 56 and 58 are rejected under the judicially created doctrine of obviousness-type double patenting as being unpatentable over claims 1-9 of U.S. Patent No. 6,296,557. Although the conflicting claims are not identical, they are not patentably distinct from each other because even though Patent No. 6,296,557 (Walker) does not specifically disclose varying the removal rates of material from the substrate by biasing it relative to the planarizing medium, it would have been obvious to one of ordinary skill in the art at the time the invention was made to have biased the substrate of Walker relative to the planarizing surface thus impacting the pressure on the surface and hence the planarizing rate.

Conclusion

Applicant's amendment necessitated the new ground(s) of rejection presented in this Office action. Accordingly, **THIS ACTION IS MADE FINAL**. See MPEP § 706.07(a). Applicant is reminded of the extension of time policy as set forth in 37 CFR 1.136(a).

A shortened statutory period for reply to this final action is set to expire THREE MONTHS from the mailing date of this action. In the event a first reply is filed within TWO MONTHS of the mailing date of this final action and the advisory action is not mailed until after the end of the THREE-MONTH shortened statutory period, then the shortened statutory period will expire on the date the advisory action is mailed, and any extension fee pursuant to 37 CFR 1.136(a) will be calculated from the mailing date of the advisory action. In no event, however, will the statutory period for reply expire later than SIX MONTHS from the date of this final action.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Alvin J Grant whose telephone number is (703) 305-3315. The examiner can normally be reached on Mon-Fri 8:00-4:30.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Joseph J Hail can be reached on (703) 308-2687. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

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Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

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Joseph J. Hail, III Supervisory Patent Examiner Technology Center 3700

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